

IN THE CLAIMS

1. (currently amended) An integrated inspection system adapted to inspect a substrate, the integrated inspection system comprising:
 - a first inspection station adapted to perform a first inspection of the substrate at a first resolution and for identifying defect candidate sites, the first inspection station disposed at a first known location,
 - a controller adapted to determine and track position information associated with each of the identified defect candidate sites,
 - a second inspection station adapted to perform a second inspection of the defect candidate sites at a second resolution, where the second resolution is higher than the first resolution, the second inspection station disposed at a second known location, and
 - a substrate stage adapted to move the substrate between the first known location of the first inspection station and the second known location of the second inspection station, and to move the substrate under both the first inspection station and the second inspection station,
where the controller positions the substrate stage at the identified defect candidate sites under the second inspection station using known coordinates of the first known location, the second known location, and the position information associated with each of the identified defect candidate sites, and without re-acquiring a coordinate system of the first inspection station when the substrate is transferred to the second inspection station.
2. (original) The integrated inspection system of claim 1, wherein the first inspection station is an optical inspection station.
3. (original) The integrated inspection system of claim 1, wherein the second inspection station is a scanning probe microscope.
4. (original) The integrated inspection system of claim 1, wherein the second inspection station is an atomic force microscope.

5. (original) The integrated inspection system of claim 1, wherein the second inspection station is a near field scanning optical microscope.
6. (original) The integrated inspection system of claim 1, wherein the second inspection station is a magnetic force microscope.
7. (original) The integrated inspection system of claim 1, wherein the second inspection station is a scanning tunneling microscope.
8. (original) The integrated inspection system of claim 1, wherein a distance between the first inspection station and the second inspection station is fixed and known by mechanically referencing critical components of the first inspection station and the second inspection to a common structure.
9. (currently amended) A method for inspecting a substrate, the method comprising the steps of:
 - a) positioning the substrate at a first inspection station using a substrate stage,
 - b) imaging a surface of the substrate at a first resolution using the first inspection station,
 - c) identifying defect candidate sites on the surface of the substrate,
 - d) determining and tracking position information associated with each of the identified defect candidate sites,
- 5 | 10 | 15 | a(e) positioning the substrate at a second inspection station using the substrate stage, and
 - e(f) imaging the defect candidate sites using the second inspection station, where the substrate is positioned at the identified defect candidate sites under the second inspection station using known coordinates of the first inspection station and the second inspection station, and the position information associated with each of the identified defect candidate sites, and without re-acquiring a coordinate system of the first inspection station when the substrate is positioned at the second inspection station.

10. (currently amended) The method of claim 82, wherein steps a-e are performed under the control of a controller connected to the first inspection station, the second inspection station, and the substrate stage.

11. (original) The method of claim 9, wherein the second inspection station is a scanning probe microscope.

12. (original) The method of claim 9, wherein the second inspection station is an atomic force microscope.

13. (original) The method of claim 9, wherein the second inspection station is a near field scanning optical microscope.

14. (original) The method of claim 9, wherein the second inspection station is a magnetic force microscope.

15. (original) The method of claim 9, wherein a distance between the first inspection station and the second inspection station is fixed and known by mechanically referencing critical components of the first inspection station and the second inspection to a common structure.

16. (currently amended) A method for optimizing inspection parameters of an integrated inspection system, the method comprising the steps of:

- positioning a substrate at a first inspection station using a substrate stage,
- imaging a surface of the substrate at a first resolution using the first inspection station,
- identifying defect candidate sites on the surface of the substrate based on the inspection parameters,
- determining and tracking position information associated with each of the identified defect candidate sites,
- positioning the substrate at a second inspection station using the substrate stage,

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15 e) imaging the defect candidate sites at a second resolution using the second
 inspection station, where the second resolution is greater than the first
 resolution, where the substrate is positioned at the identified defect
 candidate sites under the second inspection station using known
 coordinates of the first inspection station and the second inspection
 station, and the position information associated with each of the identified
 defect candidate sites, and without re-acquiring a coordinate system of the
 first inspection station when the substrate is positioned at the second
 inspection station,
20 f) reviewing the defect candidate sites imaged with the second inspection
 station to determine which of the defect candidate sites are actual defect
 sites, and
25 g) altering the inspection parameters based on the determination of which of
 the defect candidate sites are actual defect sites.

17. (original) The method of claim 16, wherein steps a-g are performed automatically
with a controller connected to the first inspection station, the second inspection
station, and the substrate stage.

18. (original) The method of claim 16, wherein the second inspection station is an
atomic force microscope.

19. (original) The method of claim 16, wherein the second inspection station is a near
field scanning optical microscope.

20. (original) The method of claim 16, wherein the second inspection station is a
magnetic force microscope.